Patent

Case No.: 57389US004



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

First Named Inventor:

THEISS, STEVEN D

Application No.:

Group Art Unit:

Filed:

November 21, 2003

Examiner:

Unknown

Title:

METHOD OF MAKING TRANSISTORS

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Pursuant to 37 CFR §§ 1.56, 1.97, and 1.98, enclosed is a completed Form PTO-1449, citing references submitted for consideration by the Examiner. Copies of any cited foreign patents, non-patent literature, and unpublished US application documents are enclosed. Pursuant to the waiver in the Pre-OG Notice, dated July 11, 2003, copies of US patents and published US patent applications are no longer required and are not enclosed. It is respectfully requested that the Examiner initial and return the enclosed Form PTO-1449 to indicate that each reference has been considered.

By:

Respectfully submitted,

Date

Kent S. Kokko, Reg. No.: 33,931

Telephone No.: (651) 733-3597

Office of Intellectual Property Counsel 3M Innovative Properties Company Facsimile No.: 651-736-3833

Nov 21,2003

Substitute for form 1449A/PTO (modified)

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Filing Date	N v mber 20, 2003		
First Named Invent r	Theiss, Stev n D		
Art Unit			
Examiner Name			
Attorney Case Number	57389US004		

U.S. Patent Documents						
		Document Number	Publication Date or		(This field is not required	
Exam. Init.*	Cite No.	Doc. Number-(Kind Code if Known) (Add Kind Code after patent No. when available)	Issue Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
	A1	US- 2002/0195929 A1	12/26/2002	Haase et al.		
	A2	US- 2003/0100779 A1	05/29/2003	Vogel et al.		
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		Ctry. Code	Number-KindCode (If known)	Publication Date MM-DD-YYYY	required)Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Translation (Check if yes)
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	B4	wo	00/10196	02/24/2000			
	B5						, ,
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Date Considered:

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Art Unit			
Examiner Name			
Attorney Case Number	57389US004		

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS
Exam. Init.*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published
	C1	S. M. SZE, Physics of Semiconductor Devices, (1981), pp. 438-442, 492-493, 2 nd Edition, John Wiley & Sons, New York
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